

Fig. 1

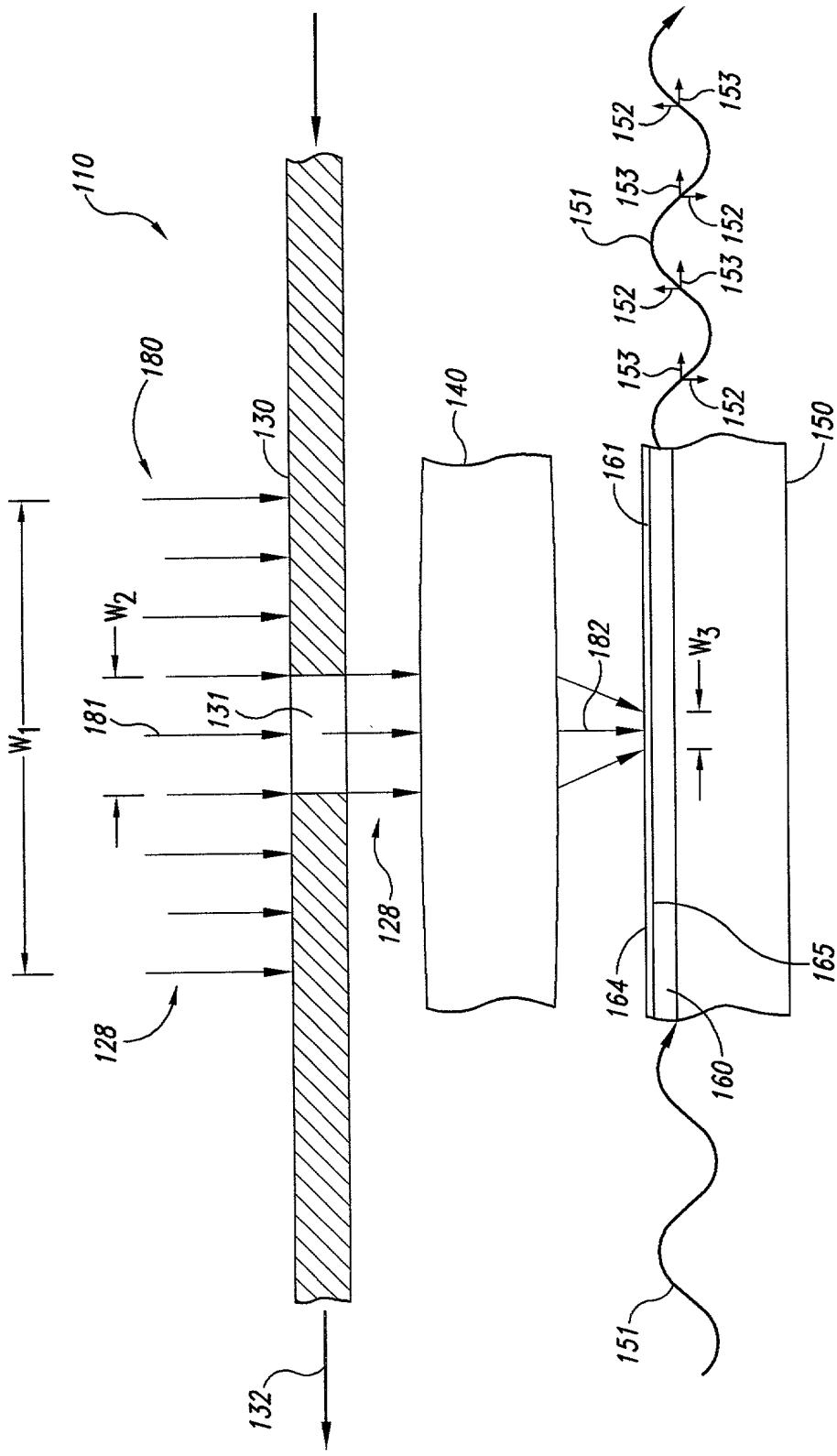


Fig. 2

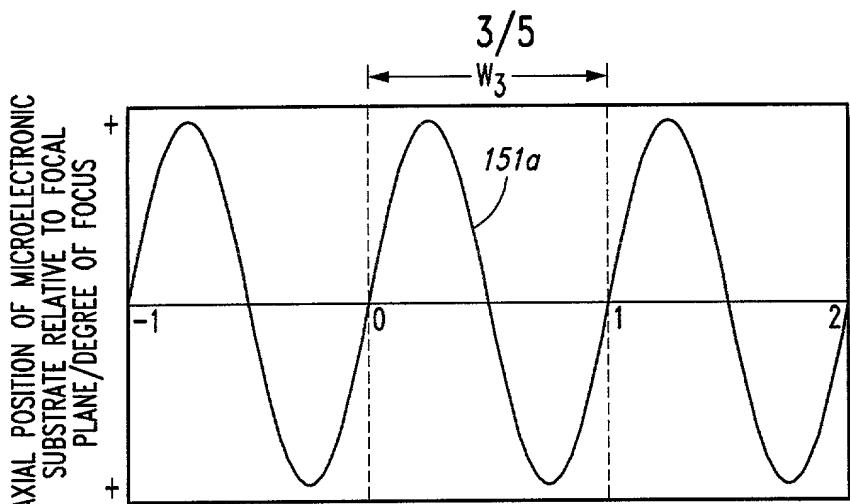


Fig. 3A

TRANSVERSE POSITION OF MICROELECTRONIC SUBSTRATE
(NORMALIZED TO MOTION RELATIVE TO BEAM OF ONE BEAM WIDTH (W_3)
AT THE MICROELECTRONIC SUBSTRATE)

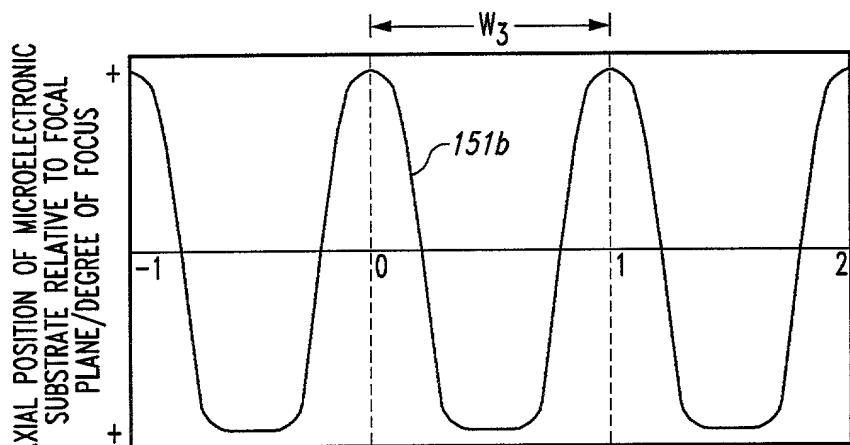


Fig. 3B

TRANSVERSE POSITION OF MICROELECTRONIC SUBSTRATE
(NORMALIZED TO MOTION RELATIVE TO BEAM OF ONE BEAM WIDTH (W_3)
AT THE MICROELECTRONIC SUBSTRATE)

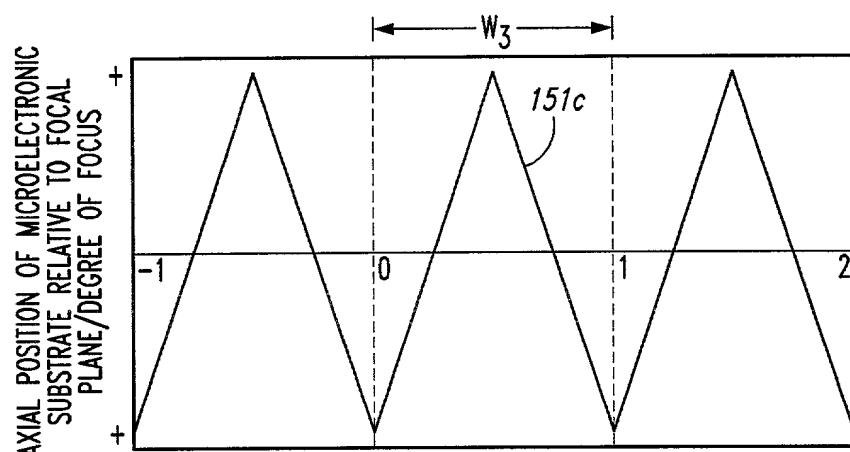


Fig. 3C

TRANSVERSE POSITION OF MICROELECTRONIC SUBSTRATE
(NORMALIZED TO MOTION RELATIVE TO BEAM OF ONE BEAM WIDTH (W_3)
AT THE MICROELECTRONIC SUBSTRATE)

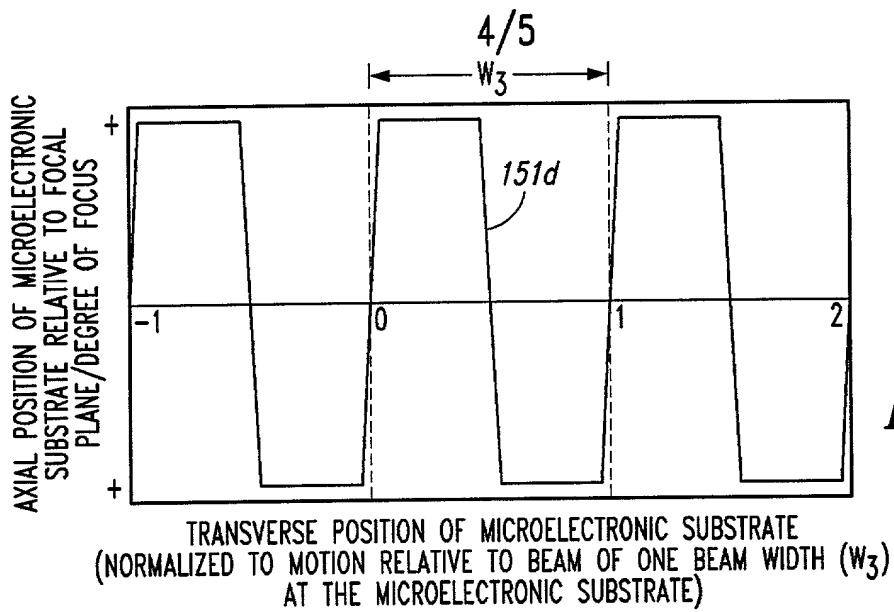


Fig. 3D

TRANSVERSE POSITION OF MICROELECTRONIC SUBSTRATE
(NORMALIZED TO MOTION RELATIVE TO BEAM OF ONE BEAM WIDTH (W_3)
AT THE MICROELECTRONIC SUBSTRATE)

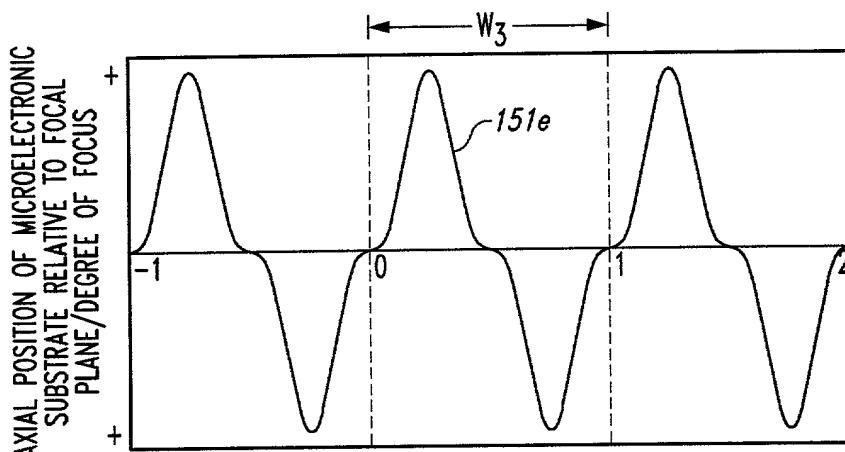


Fig. 3E

TRANSVERSE POSITION OF MICROELECTRONIC SUBSTRATE
(NORMALIZED TO MOTION RELATIVE TO BEAM OF ONE BEAM WIDTH (W_3)
AT THE MICROELECTRONIC SUBSTRATE)

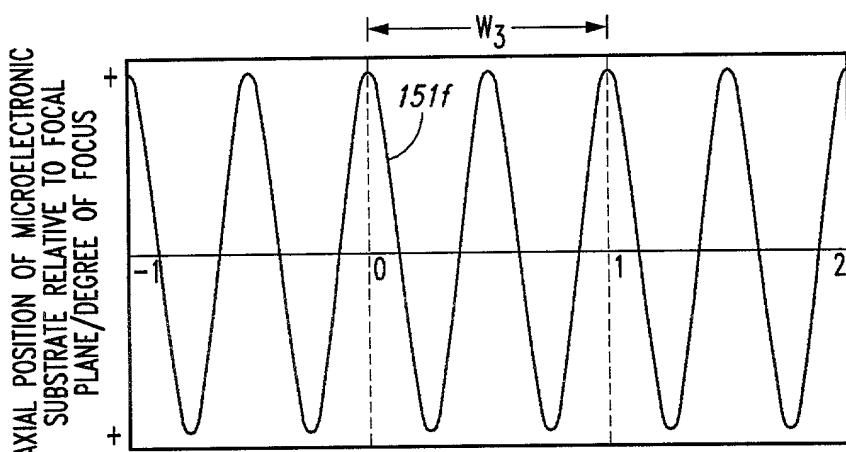


Fig. 3F

TRANSVERSE POSITION OF MICROELECTRONIC SUBSTRATE
(NORMALIZED TO MOTION RELATIVE TO BEAM OF ONE BEAM WIDTH (W_3)
AT THE MICROELECTRONIC SUBSTRATE)

5/5

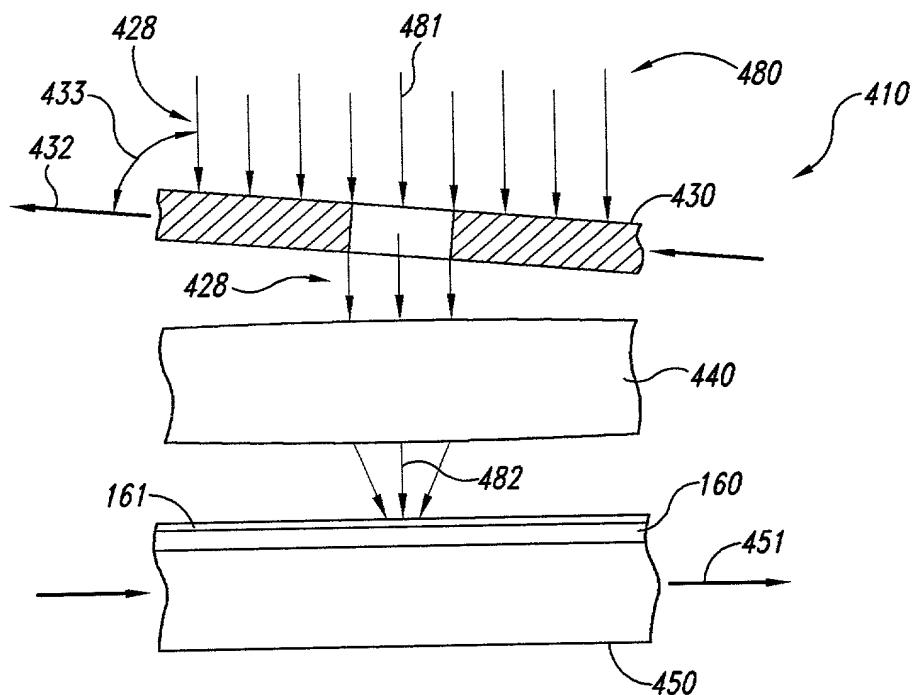


Fig. 4

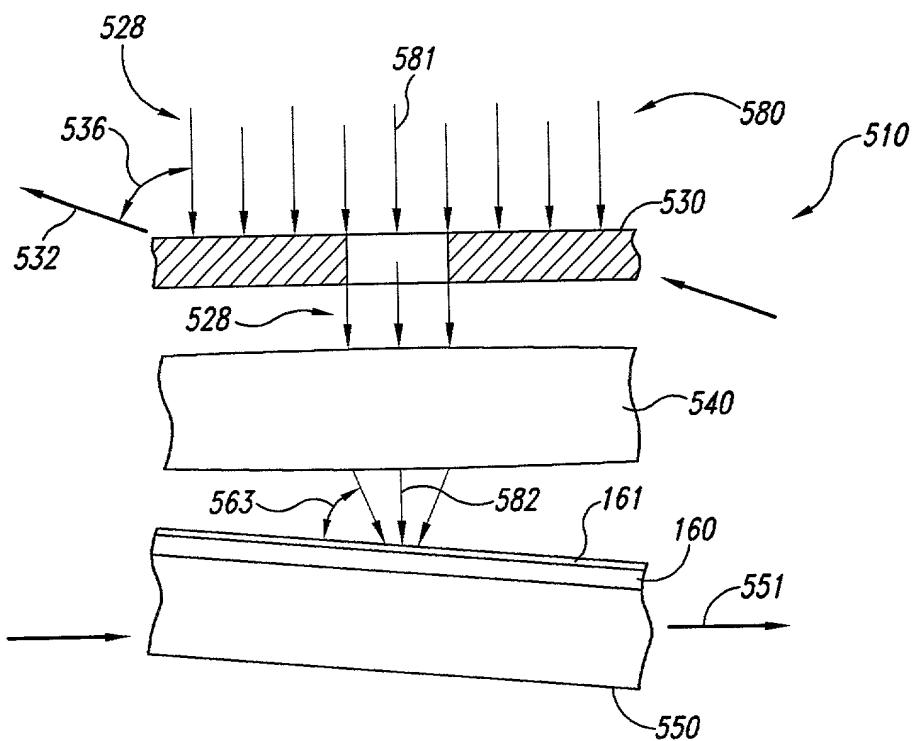


Fig. 5